

Title (en)

TREATMENT OF OXIDABLE GAS GENERATED FROM WASTE AT A DUMPING AREA

Title (de)

BEHANDLUNG VON OXIDIERBAREM DEPONIEGAS

Title (fr)

TRAITEMENT DE GAZ OXYDABLES PROVENANT DE DECHETS DANS UNE ZONE DE DEVERSEMENT

Publication

EP 1216110 B1 20031119 (EN)

Application

EP 00958539 A 20000901

Priority

- FI 0000738 W 20000901
- FI 19991877 A 19990902

Abstract (en)

[origin: US6644890B1] A method for treating oxidable gas generated from waste at a dumping area and to the structure of the dumping area. The dumping area has an organic waste layer covered with a sealing layer that prevents the absorption of water, with a drying layer and a surface layer. Oxidable gas is generated and directed through an aperture formed in the sealing layer and made to spread in, the lateral direction with the help of one or several flow controllers so that the gas ends in the surface layer to become biologically oxidized. The aperture may be provided with a cover, and the gas flow controllers may be perforated pipes extending radially from a side of a well. The oxidation of gas may be intensified by directing air and/or moisture from a piping to the surface layer.

IPC 1-7

B09B 1/00

IPC 8 full level

B01D 53/85 (2006.01); **B09B 1/00** (2006.01); **B09C 1/00** (2006.01)

CPC (source: EP US)

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